

Modeling Radiation Damage Effects in Oxygenated Silicon Detectors

M. Petasecca ^(1,2), *G.U. Pignatel* ^(1,2), *G. Caprai* ⁽¹⁾, *D. Passeri* ^(1,2)



(1) University of Perugia, via G.Duranti 93 - 06125 Perugia ITALY



(2) INFN sez. Perugia, via Pascoli 10 – 06120 Perugia ITALY

OUTLINE

- **Introduction: modeling set-up**
- **Summary of present p-type and n-type Silicon radiation damage models**
- **Results on proton irradiated FZ Oxygen Enriched Silicon (DOFZ)**
- **Conclusions**

Geometrical Definition of the simulated structure

Sample structure: **PAD detector** with a Guard Ring (1 μ m toward the 3rd direction)

<111> FZ – Substrate:

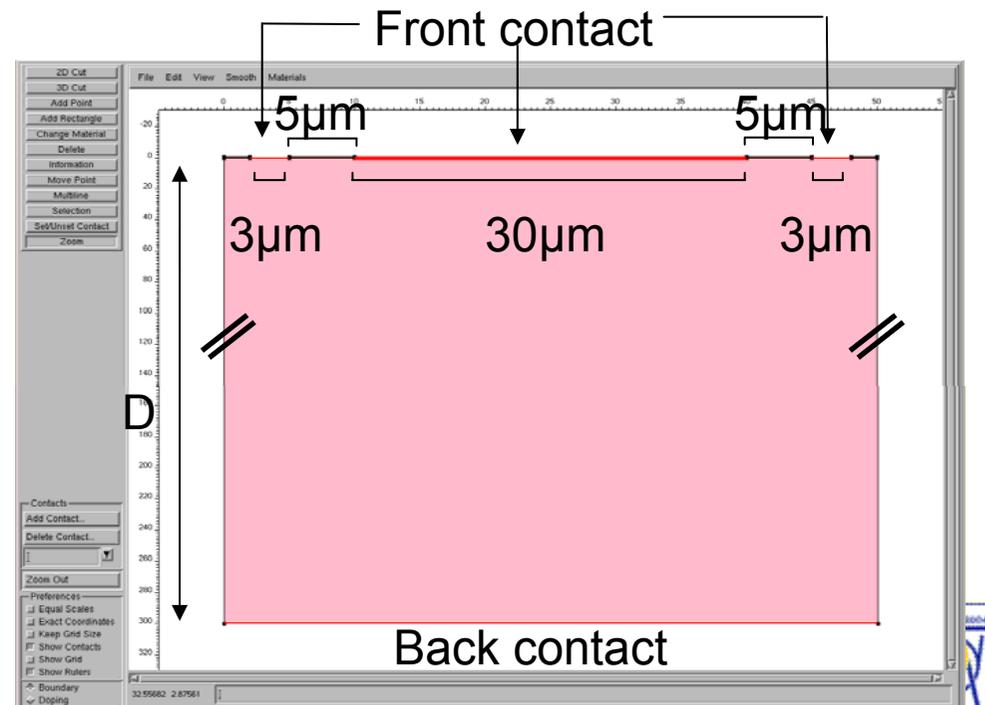
- n-doped ($7 \times 10^{11} \text{ cm}^{-3}$) \rightarrow 6k Ω cm
- p-doped ($5 \times 10^{12} \text{ cm}^{-3}$) \rightarrow 3k Ω cm
- Charge concentration at the silicon-oxide interface:
 - $4 \times 10^{11} \text{ cm}^{-3}$ pre-irradiation
 - $1 \times 10^{12} \text{ cm}^{-3}$ post-irradiation

Thickness:

p-type devices $D = 300\mu\text{m}$

n-type devices with different thickness:

$D = 50\text{-}100\text{-}300 \mu\text{m}$



Defect Energy Levels

Assignement	Energy Level	Conc.
$VO^{(-/0)}$	$E_c - 0.17 \pm 0.01$ eV	$6 \div 7 \times 10^{11} \text{cm}^{-3} / \text{Mrad}^{**}$
$V_2^{(-/0)}$ (neutron irradiation)	$E_c - 0.415 \pm 0.015$ eV	$1.0 \times 10^{10} \text{cm}^{-3} / \text{Mrad}^{**}$
E(240) $V_2O^{(-/0)}$ (gamma irradiation)	$E_c - 0.545$ eV	$0.8 \times 10^9 \text{cm}^{-3}$ ***
$\Gamma - (V_2O - V_3 ?)$ (p+,e- irradiation)	$E_c - 0.46$ eV	$9.6 \times 10^9 \text{cm}^{-3}$ *
H(160) $CI_{Oi}^{(+/0)}$	$E_v + 0.37 \pm 0.01$ eV	$4 \div 7 \times 10^{10} \text{cm}^{-3} / \text{Mrad}^{**}$

VO, always present in DLTS spectra, important because $VO + V \rightarrow V_2O$

[*] CERN-LHCC-2003-058 RD50 Status Report 2003.

[**] Pintilie Ioana, RESMDD'06, Florence 10-13 October 2006.

[***] visible only on high resistivity Si above 15Mrad of γ irradiation.

[*] Pirollo et al. "Radiation damage on p-type silicon detectors" NIM A 426 (1999)



Radiation Damage Model: P-TYPE Si

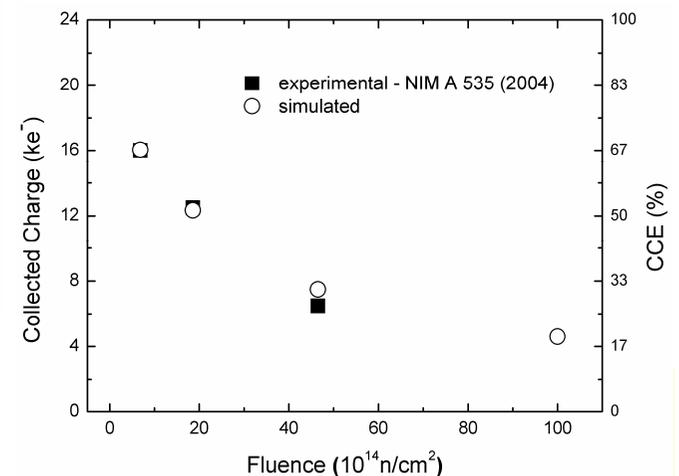
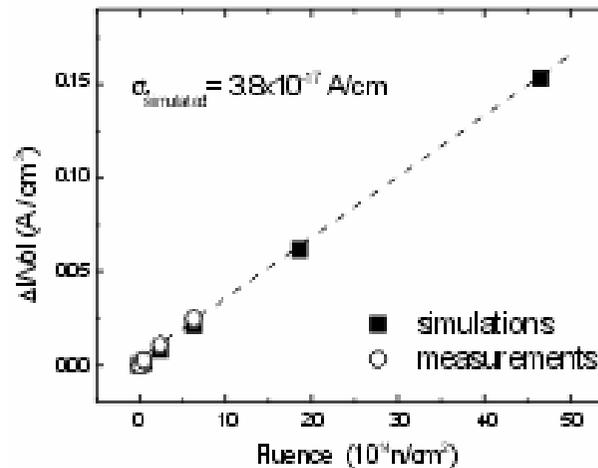
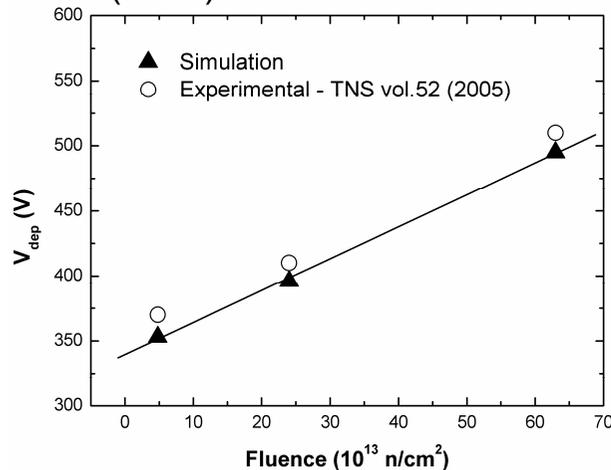
Level	Ass.	$\sigma_n(\text{cm}^2)$	$\sigma_p(\text{cm}^2)$	$\eta(\text{cm}^{-1})$	Ref.
$E_C - 0,42\text{eV}$	$VV^{(-/0)}$	$2\text{e-}15$	$2\text{e-}14$	1,613	[2]
$E_C - 0,46\text{eV}$	$VVV^{(-/0)}$	$5\text{e-}15$	$5\text{e-}14$	0,9	[1,3]
$E_V + 0,36\text{eV}$	C_iO_i	$2,5\text{e-}14$	$2,5\text{e-}15$	0,9	[1,2,3]

Note: in p-type Si the 0.46 level is not attributed to V_2O but to V_3 (vacancy related defects)

[1] Pirollo et al. "Radiation damage on p-type silicon detectors" NIM A 426 (1999)

[2] Zangenberg et al "On-line DLTS investigations of the mono and divacancy in p-type Si" NIM B 186 (2002)

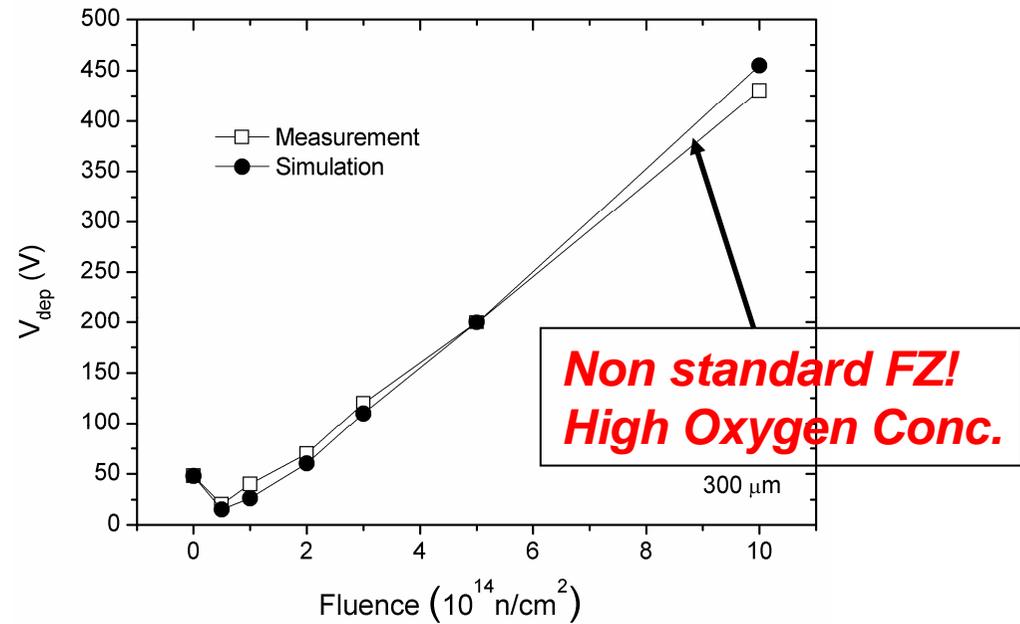
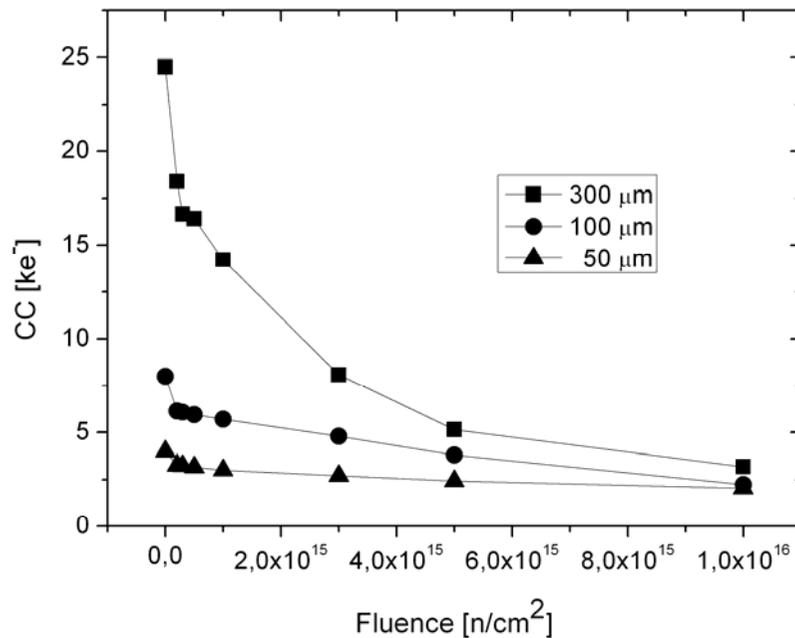
[3] Ahmed et al. "DLTS studies of Si detectors after 24GeV p irradiation and 1 MeV neutron irradiation" NIMA 457 (2001)



Radiation Damage Model: N-TYPE Si

Level	Ass.	$\sigma_n(\text{cm}^2)$	$\sigma_p(\text{cm}^2)$	$\eta(\text{cm}^{-1})$	Ref.
$E_C - 0,42\text{eV}$	$VV^{(-/0)}$	$2.2\text{e-}15$	$1.2\text{e-}14$	13	[*]
$E_C - 0,50\text{eV}$	V_2O	$4\text{e-}15$	$3.5\text{e-}14$	0.08	[*]
$E_V + 0,36\text{eV}$	C_iO_i	$2\text{e-}18$	$2.5\text{e-}15$	1.1	[*]

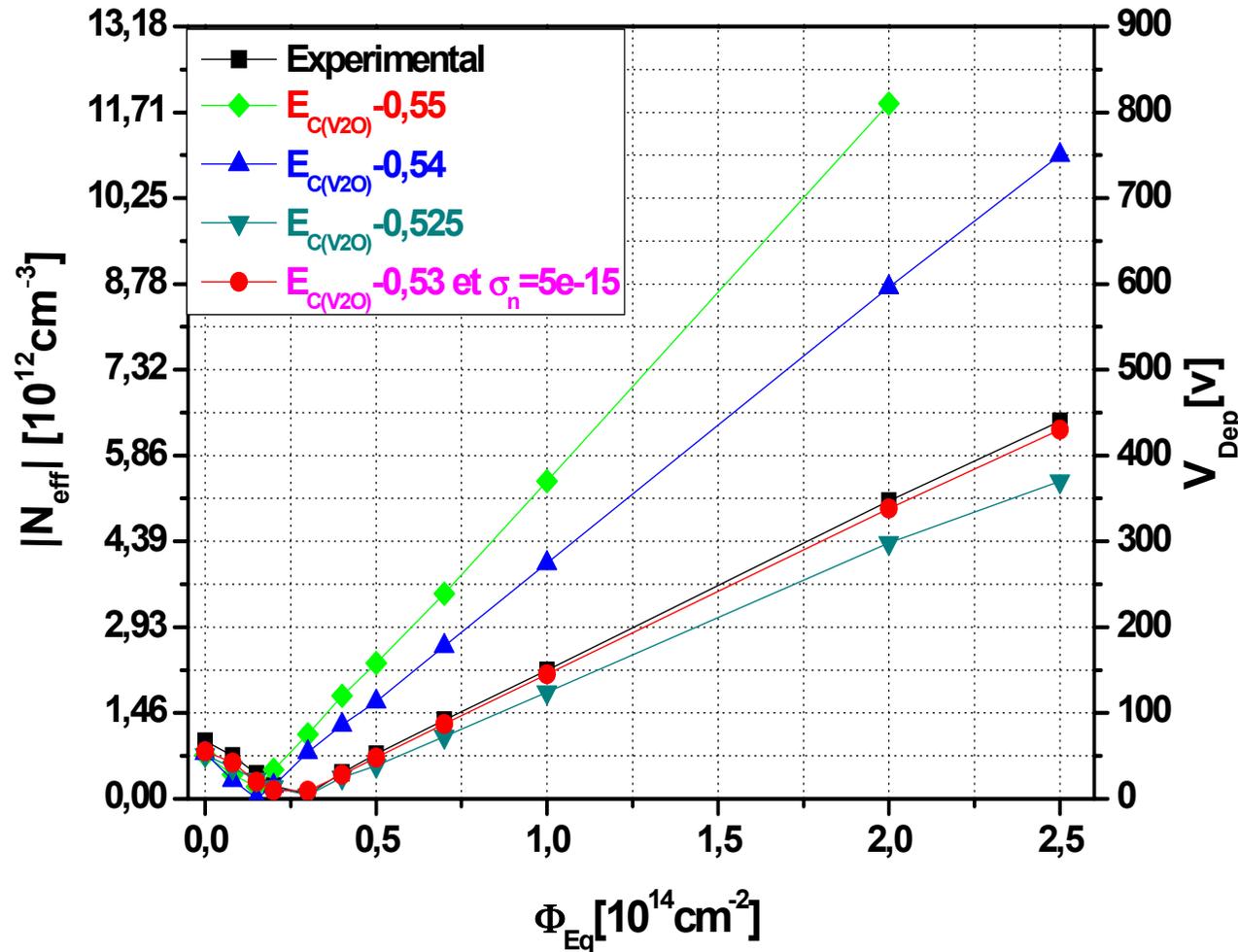
[*] M.Petasecca, F.Moscatelli, D.Passeri, and G.U.Pignatell, IEEE TNS 53-5 (2006) 1-6.



samples from SMART collaboration

Standard FZ n-type Si, 23GeV proton irradiated

Standard FZ n-Type



Standard Fz n-Type [WE - 7k]

$N_{\text{eff}0} = 7 \times 10^{11} \text{ cm}^{-3}$
 $g_c \cdot N_0 = 0,03$
 (donor removal constant)

$\rho = 6 \text{ k}\Omega\text{cm}$
 (substrate resistivity)

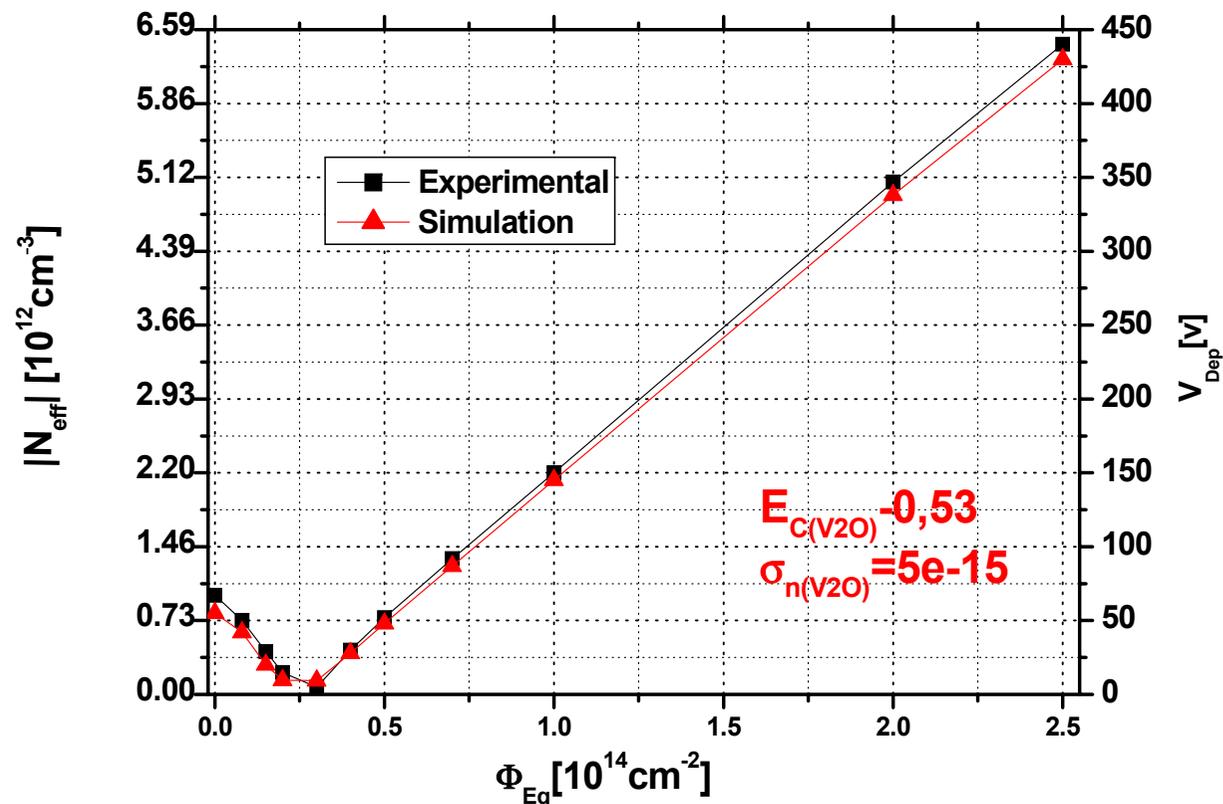
$[O_i] < 3 \div 5 \times 10^{16} [\text{cm}^{-3}]$

crystal orientation $\langle 111 \rangle$

Experimental data from Lindstrom G. et al., NIM A 466 (2001) – RD48-ROSE

Level	Ass.	$\sigma_n(\text{cm}^2)$	$\sigma_p(\text{cm}^2)$	$\eta(\text{cm}^{-1})$
$E_C - 0,42\text{eV}$	VV ⁽⁻⁰⁾	2e-15	1,2e-14	13
$E_C - 0,53\text{eV}$	VVO	5e-15	5e-14	0,08
$E_V + 0,36\text{eV}$	C _i O _i	2,5e-14	2,5e-15	1,1

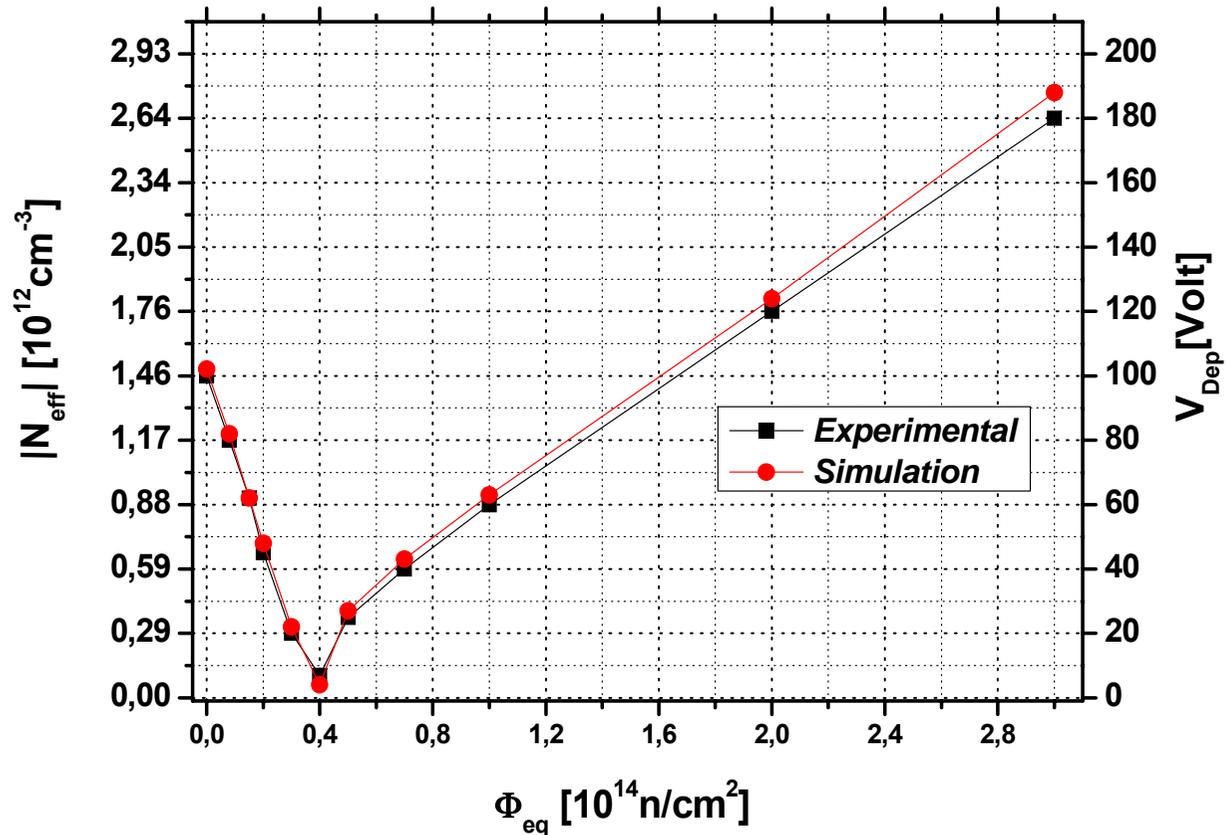
Fz- Standard 300 micron



Experimental data from Lindstrom "Radiation damage in silicon detectors"
Nuclear Instruments and Method in Physics Research A 512 (2003) 30-43

DOFZ n-type Si, 23 GeV proton irradiated

n-Type Oxigenated



Oxygen rich Fz n-Type
[WS – 3k]

$$N_{eff0} = 1,5 \times 10^{12} \text{ cm}^{-3}$$

$$g_c * N_0 = 0,03$$

(donor removal constant)

$$\rho = 3 \text{ k}\Omega\text{cm}$$

(substrate resistivity)

$$[O_i] = 1.5 \times 10^{17} [\text{cm}^{-3}]$$

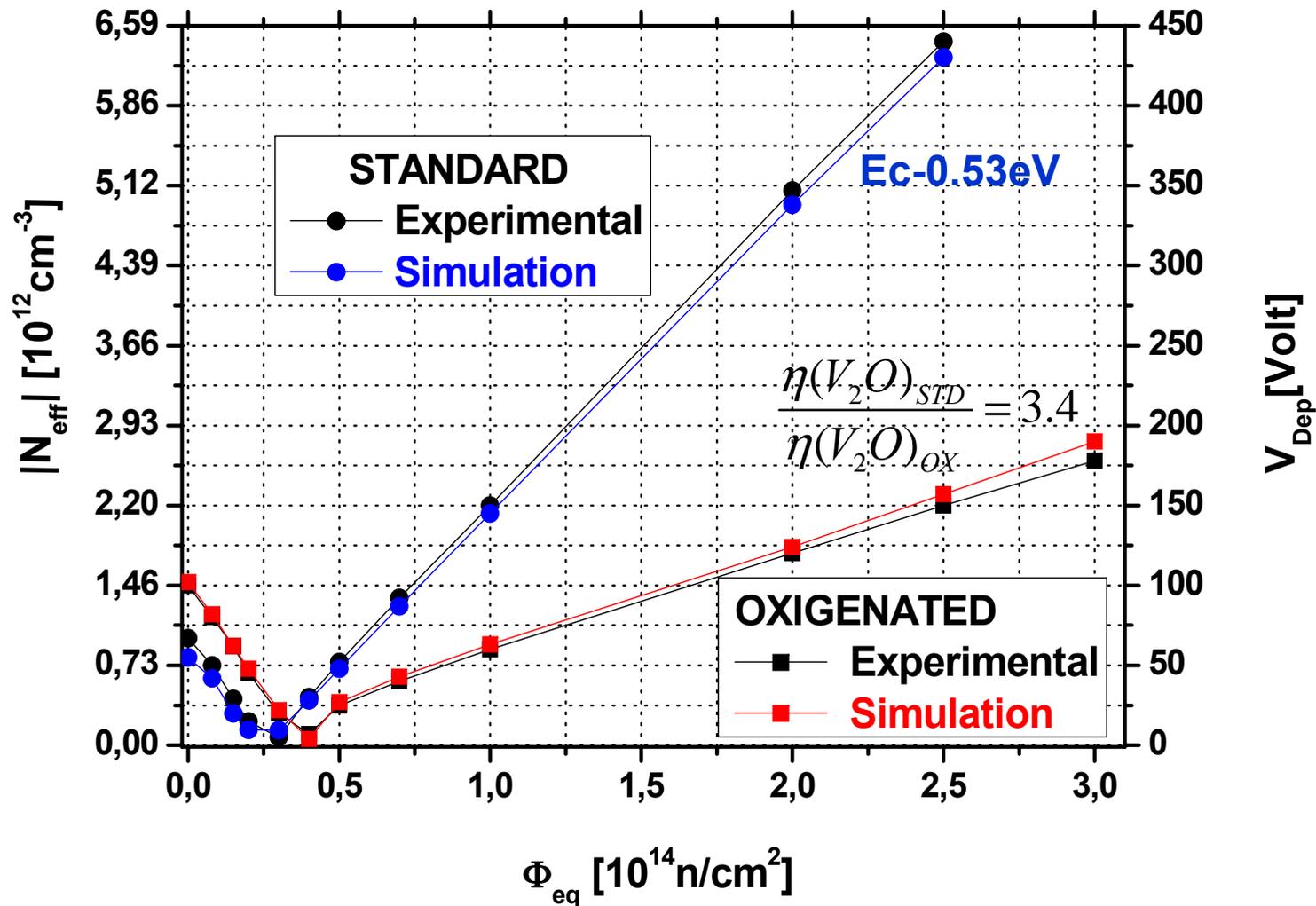
crystal orientation <111>

Experimental data from Lindstrom "Radiation damage in silicon detectors"
Nuclear Instruments and Method in Physics Research A 512 (2003) 30-43

Ratio of acceptors Introduction rates between
Standard-FZ and Oxigenated-FZ (DOFZ)

$$\frac{\eta(V_2O)_{Std}}{\eta(V_2O)_{Ox}} = 3,4$$

Comparison between Stand. FZ (n-type) and DOFZ Si, 23GeV proton irradiated



Conclusions

All the simulations made so far, compared with experimental data, are consistent with the following defect model scenario:

- $V_2 \rightarrow E_c - 0.42 \div 0.43 \text{eV}$ ($\eta \gg 1 \rightarrow n$ irradi., clusters)
- $C_i O_i \rightarrow E_v + 0.36 \text{eV}$ (trap for holes \rightarrow CCE)
- Γ ($V_2 O$ or V_3 ?) $\rightarrow E_c - 0.46 \text{eV}$ (p, e irradiation)
- $V_2 O \rightarrow E_c - 0.53 \div 0.545 \text{eV}$ (p, γ irradiation)

$V_2 O$ level very sensitive to initial O_2 concentration !

p-type puzzle: $E_c - 0.46$ is NOT attributed to $V_2 O$ (!?!)

Oxygenated p-type ?